

Journal of Alloys and Compounds 408-412 (2006) 538-542

Journal of ALLOYS AND COMPOUNDS

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Fabrication and properties of Er-substituted BaNb₂O₆ thin films through a chemical route

Wataru Sakamoto^{a,*}, Masanari Mizuno^b, Toshiaki Yamaguchi^b, Koichi Kikuta^b, Shin-ichi Hirano^b

^a EcoTopia Science Institute, Nagoya University, Furo-cho, Chikusa-ku, 464-8603 Nagoya, Japan ^b Department of Applied Chemistry, Graduate School of Engineering, Nagoya University, Furo-cho, Chikusa-ku, 464-8603 Nagoya, Japan

> Received 30 July 2004; received in revised form 29 September 2004; accepted 15 December 2004 Available online 24 June 2005

Abstract

Tungsten bronze (Ba,Er)Nb₂O₆ thin films have been fabricated by chemical solution deposition. Homogeneous and stable precursor solutions were prepared by controlling the reaction of starting metal-alkoxide sources in 2-ethoxyethanol. Tungsten bronze $Ba_{0.66}Er_{0.22}Nb_2O_6$ (BEN66) thin films were successfully fabricated by optimizing the several processing conditions, such as amount of Er substitution. The synthesized BEN66 thin films on Pt/MgO(1 0 0) and Pt/MgO/Si(1 0 0) substrates were found to have *c*-axis (direction of polarization) preferred orientation and to exhibit ferroelectric P–E hysteresis loops. The BEN66 thin films underwent a gradual and frequency dependent phase transition, which is the characteristic behavior along *c*-axis of tetragonal tungsten bronze niobate single crystals.

Keywords: (Ba,Er)Nb2O6; Tungsten bronze; Thin film; Preferred orientation; Chemical solution deposition; Electrical properties

1. Introduction

Tungsten bronze niobate crystals are very attractive because of their several excellent properties [1,2]. Ferroelectric tungsten bronze niobate thin films are also expected for applications in several electronic thin film devices. Therefore, the establishment of processing routes for tungsten bronze niobate thin films with desired property is very important. For several ferroelectric applications, tungsten bronze niobate thin films with *c*-axis preferred orientation are strongly required, because the *c*-axis is the direction of polarization of these substances. The advantage of these tungsten bronze niobates over other ferroelectric materials is easy to control the orientation along the direction of polarization. The authors have reported that the preparation and properties of tungsten bronze (Sr,Ba)Nb₂O₆- and (Pb,Ba)Nb₂O₆-based ferroelectric thin films with *c*-axis preferred orientation on MgO(100) and Pt/MgO(100) substrates using metal-organic precursor solutions [3–5].

Recently, rare-earth-substituted barium niobate (BaNb₂O₆)-based compounds are receiving great attention as a new ferroelectric tungsten bronze niobate material. BaNb₂O₆ does not show any ferroelectric properties, because its crystal structure is not the tungsten bronze type. BaNb₂ O_6 is reported to consist of two phases, the orthorhombic and the hexagonal metastable phase (low-temperature phase) [6]. On the other hand, rare-earth-ion-modified $BaNb_2O_6$ has the tetragonal tungsten bronze structure, according to the literature [7]. Various Ba_{3.75}Ln_{0.833}Nb₁₀O₃₀ [Ln: La–Er, Y]-type bulk ceramics were prepared by the solid-state reaction. However, further investigations to optimize the selection of rare earth elements and the amount of rareearth-ion substitution into the BaNb₂O₆ structure were required to design new ferroelectric compositions leading to a stable ferroelectric tungsten bronze phase and higher Curie temperatures for ferroelectric thin film applications [8–10]. Also, the fabrication of ferroelectric thin films on Si-based

^{*} Corresponding author. Tel.: +81 52 789 2751; fax: +81 52 789 2133. *E-mail address:* sakamoto@esi.nagoya-u.ac.jp (W. Sakamoto).

 $^{0925\}text{-}8388/\$$ – see front matter © 2005 Elsevier B.V. All rights reserved. doi:10.1016/j.jallcom.2004.12.063

substrates is indispensable for practical applications to combine with the semiconductor device processes.

We describe the fabrication of highly oriented Ersubstituted $BaNb_2O_6$ thin films of the ferroelectric tungsten bronze phase by chemical solution deposition (CSD), because the CSD process has several advantages, such as precise control of composition. In this study, Er ion is chosen as a substituent, because rare-earth-ions of relatively small radii are reported to have high Curie temperatures [7]. The effects of the Er content and substrate on the crystallization of tungsten bronze phase and the electrical properties are examined in order to synthesize tungsten bronze films with the desired crystal orientation and ferroelectric properties.

2. Experimental procedure

Ba metal, $Er(O'Pr)_3$ and $Nb(OEt)_5$ were used as starting materials for preparing a $(Ba,Er)Nb_2O_6$ precursor solution. 2-Ethoxyethanol was selected as a solvent, which was dried over molecular sieves and distilled before use. Ba metal and $Er(O'Pr)_3$ corresponding to a $(Ba_{0.75}Er_{0.167})Nb_2O_6$ (BEN75) or $(Ba_{0.66}Er_{0.22})Nb_2O_6$ (BEN66) composition were dissolved in absolute 2-ethoxyethanol. The solution was refluxed for 18 h and then mixed with Nb(OEt)₅ solution. The mixed solution was reacted again at a reflux temperature for 18 h. All the procedures were conducted in a dry N₂ atmosphere. Then, the solution was condensed to approximately 0.2 M by removing the solvent by vacuum evaporation.

Films were fabricated using the precursor solution by spincoating onto Pt(200 nm)/MgO(100), Pt(200 nm)/Ir(50 nm)/ Ti(50 nm)/SiO₂/Si(100) and Pt(200 nm)/MgO(50 nm)/ Si(100) substrates. The rotation rate of the substrate and time for spin-coating of the precursor film were set to be 3000 rpm and 30 s, respectively. After the film was heated at 300 °C for 1 h in an O₂ flow at a rate of 1 °C/min, it was heated to a crystallization temperature for 1 h, and then cooled in an O₂ flow at a rate of 5 °C/min. The coating-crystallization process was repeated several times to adjust the thickness of the film.

In order to enhance the orientation growth of films, a thin layer was prepared as a buffer layer on a substrate using a 0.01 M precursor solution under the same coating and heating conditions as described above. The precursor film was then coated onto the precrystallized buffer layer using a 0.2 M precursor solution.

Precursor powder was also prepared from the precursor solution to study the crystallographic phase after heat treatment. The solvent was removed from the precursor solution by vacuum evaporation. The precursor was dried at 100 °C, yielding a brown solid, which was then heat-treated between 600 and 1200 °C in an O₂ flow for 1 h.

The prepared powders and films were characterized by Xray diffraction (XRD) analysis using Cu K α radiation with a monochromator and by Raman microprobe spectroscopy. The electrical properties of the films were measured using a Pt top electrode deposited by dc sputtering onto the films and a Pt layer of substrates as a bottom electrode. Measurement of the dielectric properties of the films was conducted in a wafer cryostat using an LCR meter, and the temperature was varied from -190 to 190 °C under vacuum. The P–E hysteresis loops of the films were also evaluated with a ferroelectric test system at a room temperature.

3. Results and discussion

3.1. Crystallization of (Ba,Er)Nb₂O₆ precursor powder

Homogeneous and stable (Ba_{0.75}Er_{0.167})Nb₂O₆ (BEN75) and (Ba_{0.66}Er_{0.22})Nb₂O₆ (BEN66) precursor solutions with sufficient long-term stability were successfully prepared by optimizing the preparation conditions of precursor solutions. The determination of the amount of Er substitution in BaNb₂O₆ is important for the synthesis of tungsten bronze (Ba,Er)Nb₂O₆ (BEN) thin films. Therefore, prior to the fabrication of thin films, the crystallographic phase of precursor powders after heat treatment was mainly investigated by XRD.

Fig. 1 illustrates the XRD profiles of BEN75 and BEN66 precursor powders heat-treated at 800 °C. These powders were amorphous below 600 °C. In the case of BEN75 powder, a mixture of low-temperature phase similar to that of hexagonal BaNb₂O₆ and tetragonal tungsten bronze BEN was formed at 800 °C, and then the sample completely transformed into the single-phase tungsten bronze BEN above 1200 °C. Additionally, Raman spectra of BEN75 powders prepared below 1200 °C contained the scattering modes of hexagonal BaNb₂O₆ phase. The crystallization of the hexagonal BaNb₂O₆ phase has already been reported by the authors for the alkoxy-derived BaNb₂O₆ powders [8]. It revealed that a tetragonal tungsten bronze BEN phase was difficult to obtain in alkoxy-derived BEN75 with relatively small rare



Fig. 1. XRD profiles of (a) $Ba_{0.75}Er_{0.167}Nb_2O_6$ (BEN75) and (b) $Ba_{0.66}Er_{0.22}Nb_2O_6$ (BEN66) precursor powders after heat treatment at 800 °C.

earth ions such as Er. On the other hand, BEN66 precursor powder crystallized in the tetragonal tungsten bronze phase of BEN at around 800 °C, as shown in Fig. 1(b), which was about 400 °C lower than the crystallization temperature of BEN75. This is a result of adopting an appropriate stabilization condition of the optimal amount of Er substitution for the formation of tetragonal tungsten bronze BEN. The composition ratio of Ba and Er was considered to be optimized when the composition of (Ba,Er)Nb₂O₆ was set to be BEN66.

3.2. Fabrication of $(Ba, Er)Nb_2O_6$ thin films on substrates

In this study, thin film fabrication was performed using a BEN66 composition on the basis of the crystallization behavior of BEN75 and BEN66 precursor powders described in the previous section. Fig. 2 illustrates the XRD profile of BEN66 thin film on a Pt/MgO(100) substrate heat-treated at 800 °C. This film has strong 0 01 and 0 02 reflections, as shown in Fig. 2. The BEN66 thin films on Pt/MgO(100) substrates crystallized into the desired tetragonal tungsten bronze phase with 00l preferred orientation. The lattice parameters of BEN66 was calculated from the XRD data of powder sample to be a = 12.439 Å and c = 3.934 Å, respectively. The crystallization of BEN66 films with c-axis preferred orientation results from the crystallographic matching of the c-plane of BEN66 to Pt/MgO(100), similar to the cases of other alkoxy-derived tungsten bronze niobate thin films reported by the authors [3–5]. Furthermore, Raman spectrum of the BEN66 thin film revealed that the synthesized film crystallized into the tetragonal tungsten bronze phase confirmed by the comparison with that of tetragonal tungsten bronze BEN66 powder.

For practical integrated device applications, the fabrication of thin films on Si-based substrate is strongly



Fig. 2. XRD profile of BEN66 thin films on a Pt/MgO(100) substrate heat-treated at 800 °C.



Fig. 3. XRD profiles of BEN66 thin films on (a) $Pt/Ir/Ti/SiO_2/Si(100)$ and (b) Pt/MgO/Si(100) substrates heat-treated at 800 °C.

required. Therefore, BEN66 thin films were also prepared on Pt/Ir/Ti/SiO₂/Si(100) and Pt/MgO/Si(100) substrates. Fig. 3 illustrates the XRD profiles of BEN66 thin films on Pt/Ir/Ti/SiO₂/Si and Pt/MgO/Si substrates after heat treatment. In the case of BEN66 thin film on Pt/Ir/Ti/SiO₂/Si, synthesized films were polycrystalline having relatively low 00*l* preferred orientation, as shown in Fig. 3(a). On the other hand, BEN66 thin film on Pt/MgO/Si crystallized into the desired tungsten bronze phase having 00*l* preferred orientation. These results indicate that MgO layer between Pt and Si is effective in obtaining 00*l*-oriented tungsten bronze films as in the case of BEN66 films on Pt/MgO(100). Although the growth mechanism of the MgO layer is not clear now, (100)-oriented MgO may be grown on Si(100) as reported by Senzaki et al. [11]

According to the SEM observation, the synthesized films appeared crack free and dense and had a smooth surface with uniform thickness. The quality of the films was found to be sufficient for the characterization of electrical properties.

3.3. Dielectric and ferroelectric properties of (Ba,Er)Nb₂O₆ thin films

Fig. 4 shows the temperature dependence of the dielectric constant for BEN66 thin film on Pt/MgO/Si(100) substrate in the comparison with the data of BEN66 thin film on Pt/MgO(100). The thickness of the films was 0.6 μ m. In the case of BEN66 thin film on Pt/MgO/Si, the maximum dielectric constants of approximately 400 were observed at 170 °C at 10 kHz. Also, for both BEN66 thin films on Pt/MgO(100) and Pt/MgO/Si, the values of dielectric constant depend upon the frequency of measurement, as shown in Fig. 4. In addition, since the peaks of the ε -T curves were broad, the BEN66 films were found to exhibit diffuse phase transition. This behavior is a characteristic property of tungsten bronze niobate single



Fig. 4. Temperature dependence of dielectric constants of $Ba_{0.66}Er_{0.22}$ Nb₂O₆ thin films on Pt/MgO(100) and Pt/MgO/Si(100) substrates crystallized at 800 °C.

crystal along the *c*-axis [12]. The grain size of the BEN66 thin films was confirmed to be about 80–100 nm from atomic force microscope (AFM) images. The small grain size is considered to be responsible not only for the broadening of ε –*T* curves but also for the lower Curie temperature compared with reported data of (Ba,Er)Nb₂O₆ bulk ceramics [7].

On the other hand, the low dielectric constants of approximately 30–60 were observed at 1–100 kHz in the case of the BEN66 films on Pt/Ir/Ti/SiO₂/Si substrates. Also, the dielectric constant did not depend upon the temperature of measurement so much. This behavior is mainly due to the low 00*l* preferred orientation of the BEN66 film on Pt/Ir/Ti/SiO₂/Si and the large anisotropy of dielectric properties of tungsten bronze niobate crystals reported by Huang et al. [12]

Fig. 5 shows the P–E hysteresis loop of BEN66 thin film on Pt/MgO(100) measured at room temperature. The hysteresis loop of the BEN66 film showed a remanent polarization (P_r) of 3.2 μ C/cm² and a coercive field (E_c) of 30 kV/cm.



Fig. 5. P–E hysteresis loop of BEN66 thin film on a Pt/MgO(100) substrate measured at room temperature.



Fig. 6. P-E hysteresis loops of BEN66 thin films on (a) $Pt/Ir/Ti/SiO_2/Si(100)$ and (b) Pt/MgO/Si(100) substrates measured at room temperature.

Therefore, the BEN66 thin film was ferroelectric at room temperature.

Fig. 6 shows the P-E hysteresis loops of BEN66 thin films on Pt/Ir/Ti/SiO₂/Si(100) and Pt/MgO/Si(100) substrates measured at room temperature. It can be seen from Fig. 6 that the synthesized BEN66 film on Pt/Ir/Ti/SiO₂/Si did not show sufficient ferroelectricity at room temperature, because the degree of *c*-axis (direction of polarization) orientation of the film was low, as shown in Fig. 3. On the other hand, the BEN66 thin film on Pt/MgO/Si showed a typical P-E hysteresis loop at room temperature, as shown in Fig. 6(b), because the Curie temperature of the film was clearly observed approximately 170 °C at 10 kHz, as shown in Fig. 4. The P_r and E_c values of the BEN66 film on Pt/MgO/Si were found to be about $1.3 \,\mu\text{C/cm}^2$ and $20 \,\text{kV/cm}$, respectively. Although the values of dielectric constant and P_r were relatively low, the dielectric and ferroelectric behaviors of the BEN66 thin film on Pt/MgO/Si were similar to those of BEN66 on Pt/MgO(100). The current (Ba,Er)Nb₂O₆ films also require further optimization of the processing conditions in order to improve their dielectric and ferroelectric properties. Synthesis of BEN films at lower temperatures on Si-based substrates is also now in progress.

4. Conclusions

Highly oriented Er-substituted BaNb₂O₆ thin films with a tungsten bronze structure were successfully synthesized on Pt/MgO(100) and Pt/MgO/Si(100) substrates from a metalorganic precursor solution. The substitution of the Ba²⁺ site in BaNb₂O₆ by Er in the appropriate amount was quite effective in fabricating the tetragonal tungsten bronze film. The tungsten bronze Ba_{0.66}Er_{0.22}Nb₂O₆ (BEN66) thin films with preferred orientation along the direction of polarization exhibited the diffuse phase transition and the ferroelectric P–E hysteresis loops at room temperature. The ferroelectric BEN thin films developed in this study open the avenue to various thin film device applications.

Acknowledgement

This work was partly supported by The Tatematsu Foundation.

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